# Oxidation of ZrB<sub>2</sub> SiC TaSi<sub>2</sub> Materials at Ultra High Temperatures

E. Opila, J. Smith, S. Levine, and J. Lorincz NASA Glenn Research Center

ZrB<sub>2</sub> - 20v% SiC - 20v% TaSi<sub>2</sub> was oxidized in stagnant air for ten minute cycles for times up to 100 minutes at 1627°C and 1927°C. The sample oxidized at 1627°C showed oxidation resistance better than that of the standard ZrB<sub>2</sub> - 20v% SiC. The sample oxidized at 1927°C, however, showed evidence of liquid phase formation and complex oxidation products. The sample exposed at 1927°C was analyzed in detail by scanning electron microprobe and wavelength dispersive spectroscopy to understand the complex oxidation and melting reactions occurring during exposure. The as hot-pressed material shows the formation of a Zr(Ta)B<sub>2</sub> phase in addition to the three phases in the nominal composition already noted. After oxidation, the TaSi<sub>2</sub> in the matrix was completely reacted to form Ta(Zr)C. The layered oxidation products included SiO<sub>2</sub>, ZrO<sub>2</sub>, Ta<sub>2</sub>O<sub>5</sub>, and a complex oxide containing both Zr and Ta. Likely reactions are proposed based on thermodynamic phase stability and phase morphology.



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E. Opila, J. Smith, S. Levine, J. Lorincz, M. Reigel NASA Glenn Research Center Ultra-High Temperature Ceramics Conference Lake Tahoe, CA August 5, 2008

### Background



- Previous work
  - "Oxidation of ZrB<sub>2</sub>- and HfB<sub>2</sub>-based ultra-high temperature ceramics: effect of Ta additions," E. Opila, S. Levine, J. Lorincz, J. Mat. Sci. 39 [19] 5969-5977 (2004).
- Improved oxidation resistance with 20 v/oTaSi<sub>2</sub> additions to ZrB<sub>2</sub> - 20 v/o SiC at 1627°C in air up to 100 minutes
- Improved oxidation resistance attributed to Ta additions, not excess Si
- Oxidation at 1927°C resulted in excess liquid phase formation and poor oxidation resistance



### ZrB<sub>2</sub> - 20v/o SiC - 20v/o TaSi<sub>2</sub> showed improved oxidation resistance at 1627°C in air

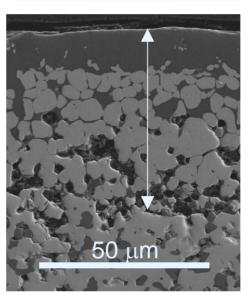
ZS: 1, 5, and 10 cycles

ZS20TS: 1, 5, and 10 cycles

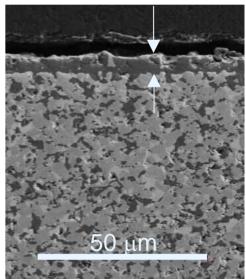


5 ZrB<sub>2</sub> - 20v/o SiC specific weight change, mg/cm<sup>2</sup> ZrB2 - 20v/o SiC - 20v/o TaSi2 0 0.00 0.50 0.75 1.00 1.25 1.50 1.75 time, hours

oxidized in 10 minute cycles



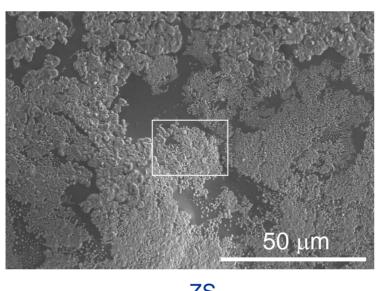
 $ZrB_2 - 20v/o SiC$ 



 $ZrB_2 - 20v/o SiC -$ 20v/o TaSi<sub>2</sub>



### Surface oxide morphology, 1627°C, 100 min, air

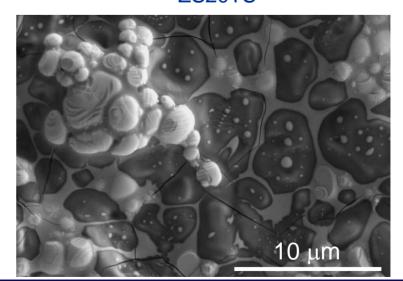


50 μm

ZS



ZS20TS





### Melt formation observed after ZS20TS oxidation at 1927°C in stagnant air







ZSTS: as-fabricated and 1 cycle

ZSTS: 5 cycles

#### Liquid phase formation a problem

- $SiO_2$ :  $T_m = 1723^{\circ}C$
- $Ta_2O_5$ :  $T_m = 1887°C$
- $Ta_2O_5.6ZrO_2$ :  $T_m>1870°C$

ZrO<sub>2</sub> provides some dimensional stability



ZS: 1, 5, and 10 cycles



### Questions arising from 1927°C exposure

- Ta distribution in oxidation products
  - is all Ta contributing to melt formation?
  - any Ta in solid phases?
- What is the composition of oxidation products?
- Can liquid phase formation be limited while still retaining improved oxidation resistance at 1627°C?



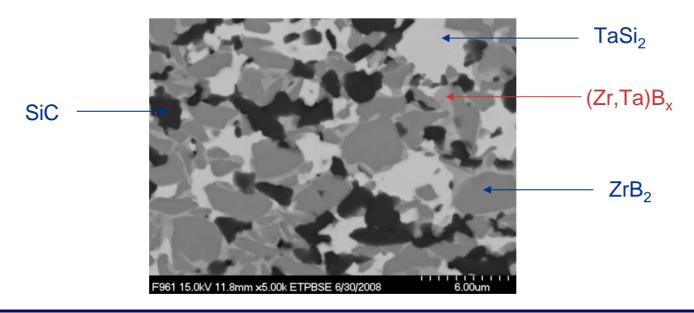
### Additional work since previous publication

- Characterization of ZS20TS after 1927°C, 5 x 10 min cycles in stagnant air
  - WDS/microprobe: JEOL 8200
  - FE-SEM: Hitachi S-4700
- Oxidation of ZS5TS at 1627°C, 1927°C for 1, 5 and 10 ten-minute cycles in stagnant air



### Characterization of ZS20TS starting material

- Desired composition: ZrB<sub>2</sub> 20v% SiC 20v% TaSi<sub>2</sub>
- As hot-pressed material shows 4 phases
  - Phase 1:  $ZrB_2$  B/Zr = 1.97
  - Phase 2: SiC C/Si = 1.08
  - Phase 3: TaSi<sub>2</sub> Si/Ta = 2.16
  - Phase 4:  $(Zr,Ta)B_{v}$  Zr/Ta = 4.19 B/(Zr+Ta) = 1.53



## Stability of TaSi<sub>2</sub>



$$\Delta G_f$$
 1927°C(kJ/mol) M+X<sub>x</sub>=MX<sub>x</sub>

TaSi <sub>2</sub>	-61
TaC	-140
TaB <sub>2</sub>	-191
TaO <sub>2.5</sub>	-615
ZrSi <sub>2</sub>	-141
ZrSi <sub>2</sub> ZrC	-141 -180
_	

- Silicides are least stable
- Zirconium compounds are more stable than tantalum compounds
- (Zr,Ta)B<sub>x</sub> formation: TaSi<sub>2</sub> reacts with excess B during hot pressing?



## ZrB<sub>2</sub> TaB<sub>2</sub> solid solution?

- ZrB<sub>2</sub> and TaB<sub>2</sub> both hexagonal crystal structure
- Limited phase stability info found

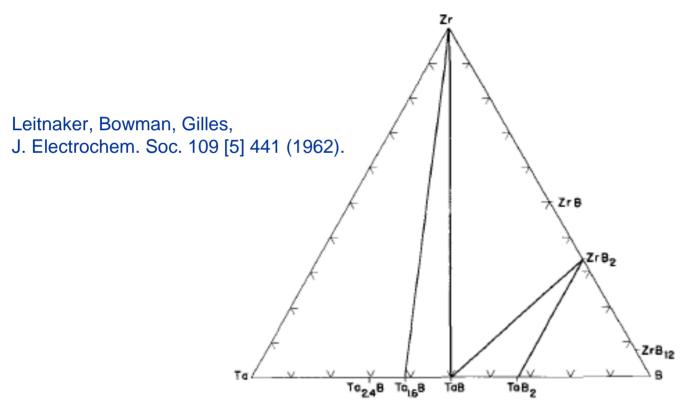


Fig. 1. Schematic phase diagram for the Ta-Zr-B system for a temperature of 1500°C.



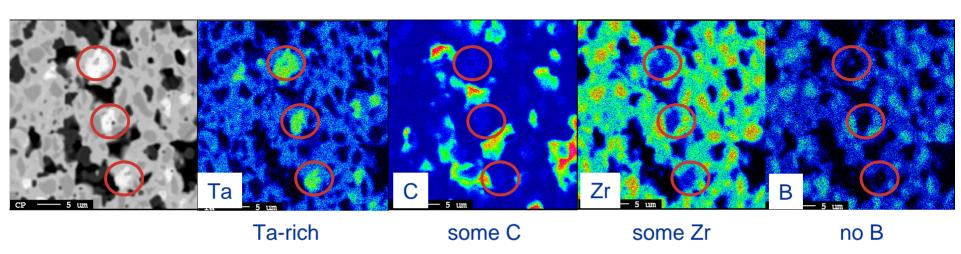
### Characterization of ZS20TS after 1927°C oxidation

- Extensive melt formation
- Characterizing phase formation after cooling
- Not necessarily equilibrium phase formation



### Characterization of ZSTS(20) after oxidation at 1927°C: matrix phases

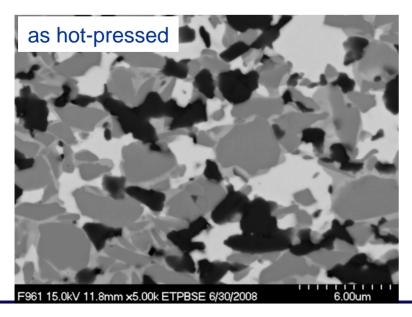
- TaSi<sub>2</sub> is gone. T<sub>m</sub> TaSi<sub>2</sub> = 2200°C (HSC, Kosolapova)
- Four phases observed:
  - Phase 1:  $ZrB_2$  B/Zr = 1.98
  - Phase 2: SiC C/Si = 1.05
  - Phase 3:  $(Zr,Ta)B_x$  Zr/Ta = 3.47 B/(Zr+Ta) = 1.43
  - Phase 4:  $(Zr,Ta)C_{\star}$  Zr/Ta = 0.56 C/(Zr+Ta) = 1.42

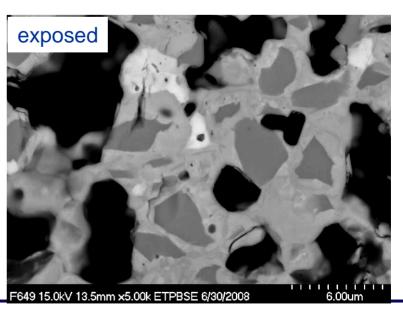




### Evolution of matrix after oxidation

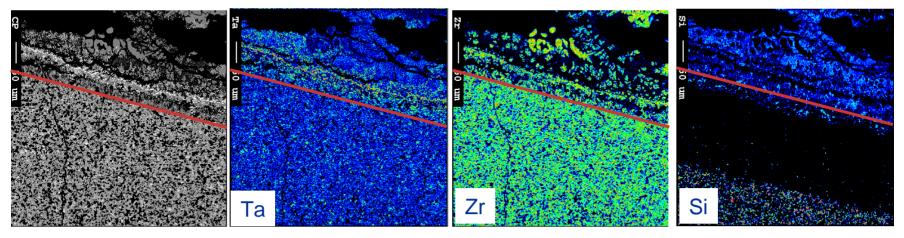
- Loss of TaSi<sub>2</sub>, appearance of TaC
  - Active oxidation of TaSi<sub>2</sub> leaving Ta?
  - TaC more stable than SiC
  - $TaSi_2 + SiC + 1.5 O_2(g) = TaC + SiO(g)$   $\Delta G_{rxn} = -79kJ/mol$
- Change in phase distribution
  - Decrease of ZrB<sub>2</sub>, SiC
  - (Increase of Zr,Ta)B<sub>x</sub>





## General characteristics of oxide layers ZS20TS 1927°C 50 minutes air



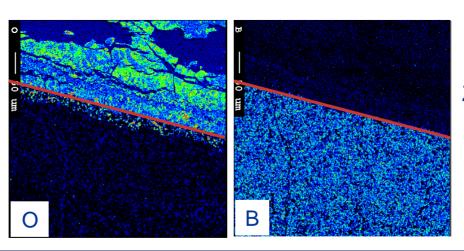


Ta concentrated near initial interface, but present throughout scale

Zr forms discrete oxide particles

Silica is present in most of scale, Si depletion layer below oxide

Oxides found below interface, silica?



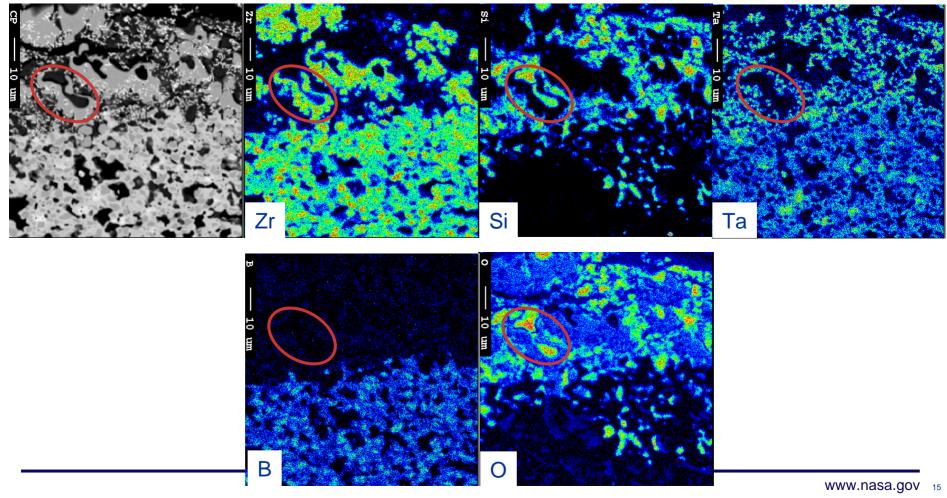
ZrB<sub>2</sub> and SiO<sub>2</sub> coexist in layer below interface. Some B in near surface oxide layer?



## Characterization of ZS20TS after oxidation at 1927°C: oxide phases adjacent to matrix

 $ZrO_2$  O/Zr = 1.96 SiO<sub>2</sub> O/Si = 1.96

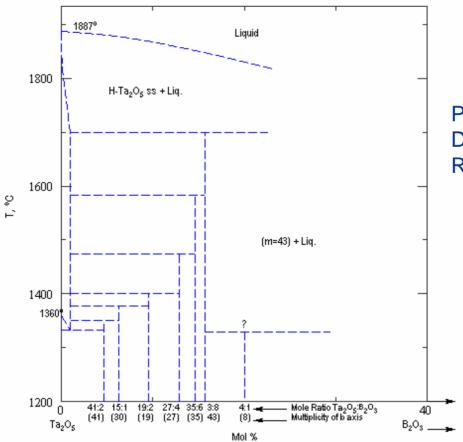
Ta(Zr)B(O) Ta/Zr = 7.49 B/O = 2.16 (B+O)/(Ta+Zr) = 1.36, not  $Ta_2O_5$ 



## (Ta,Zr)(B,O)?



- TaB<sub>2</sub> sampling ZrO<sub>2</sub> underneath small Ta-rich particles?
- Ta oxyboride?
  - Oxynitrides and oxycarbides known to exist
  - Ta O B phase diagram

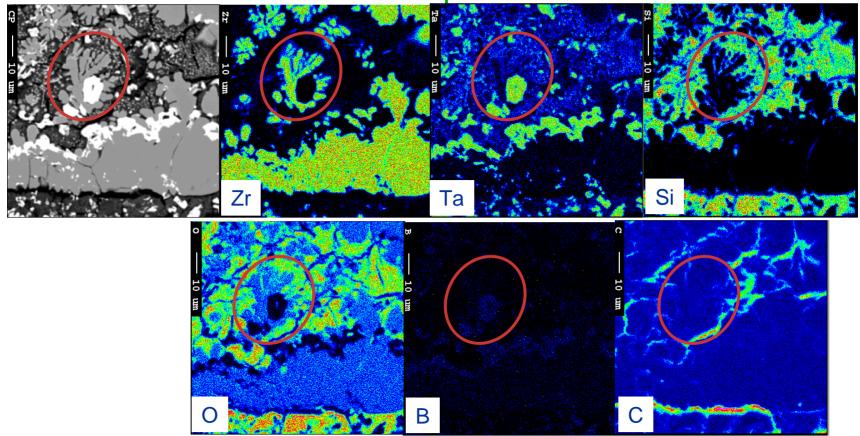


Phase Diagrams for Ceramists Diagram 4392 RS Roth, JL Waring, 1970.

### Characterization of ZS20TS after oxidation at

NASA

1927°C: middle portion of scale



 $ZrO_2$  large continuous regions O/Zr = 1.98

 $SiO_2$  O/Si = 2.39? some Ta 1.6at%

Ta(B,O) B/O = 1.71 (O+B)/Ta = 0.73 phase separated in silica

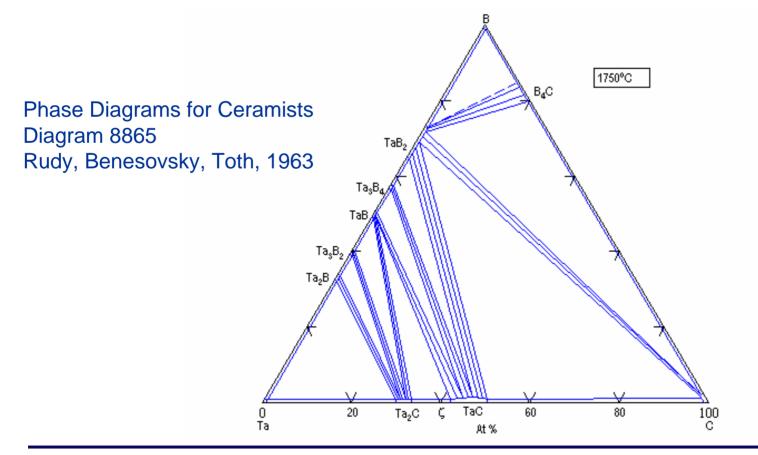
Ta(C,B) not expected: C/B = 1.34 (C+B+O)/Ta = 1.00

Additional phase not analyzed by microprobe



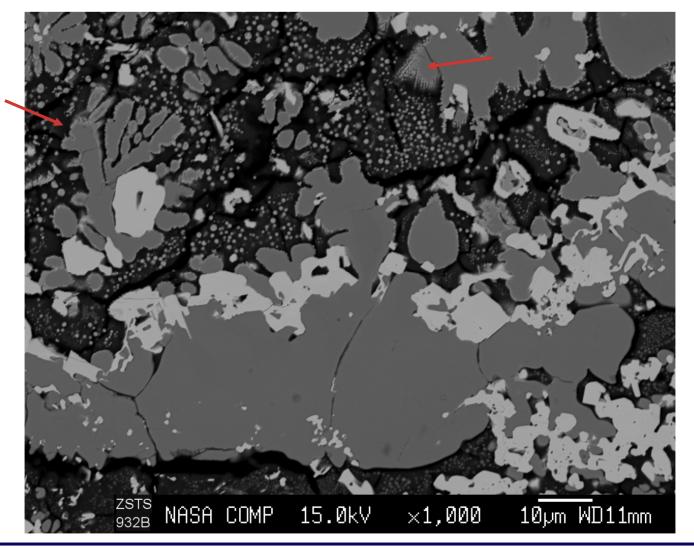
## Ta(C,B)?

- TaC and TaB<sub>2</sub> both significantly less stable than oxide phase
  - ZrO<sub>2</sub> more stable than Ta<sub>2</sub>O<sub>5</sub> (Ellingham diagram)
- Unexpected phase formation: TaC cubic, TaB<sub>2</sub> hexagonal
  - Artifact of sampling volume?





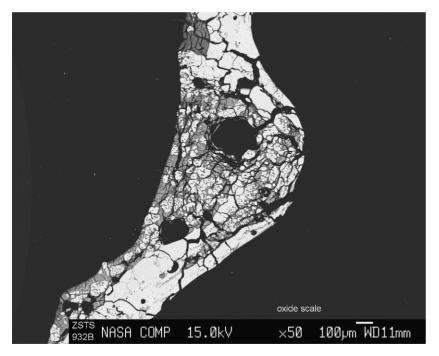
### TaZrO phase morphology on ZrO<sub>2</sub> suggests surface reaction, Phase V?

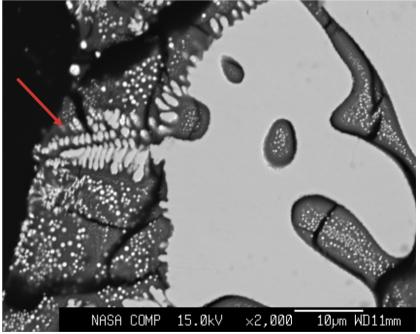




### Characterization of ZSTS(20) after oxidation at 1927°C: loose outer portion of scale

 $ZrO_2$  O/Zr = 2.07 dendrites observed  $SiO_{2}(Ta) O/(Si+Ta) = 2.917$ (Zr,Ta)O phase separated in silica Zr/Ta = 1.92, not Phase V, Zr/Ta = 5.5 to 6 O/(Zr+Ta) = 2.47, expected ratio for  $Ta_2O_5$ 

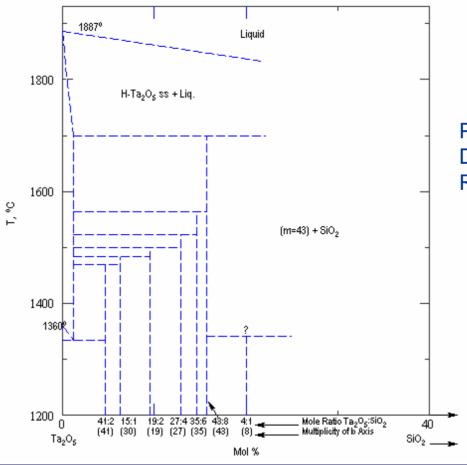




### Ta Si O



- WDS results suggest Ta-O in solution with SiO<sub>2</sub>
- Available phase diagram suggests ordering is possible



Phase Diagrams for Ceramists Diagram 4448 RS Roth, JL Waring, 1970.



### Summary of observations for ZSTS(20) oxidation at 1927C

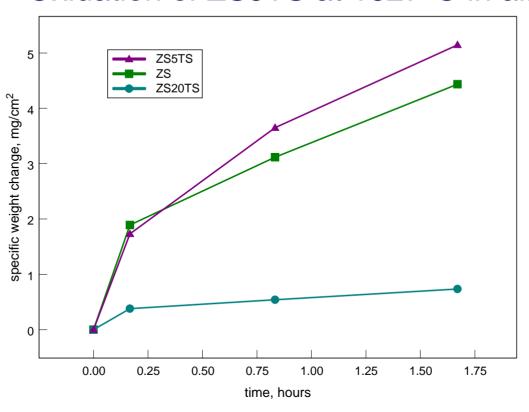
- Zr- and Ta-borides form solid solution
- TaSi<sub>2</sub> is not stable after exposure at 1927°C, about 300°C<T<sub>m</sub>
- Possible active oxidation of TaSi<sub>2</sub> resulting in SiO(g) and TaC formation
- Oxidation microstructure is fine near matrix interface, coarse at outer surface
- Ta(C,B) appears to remain unoxidized amidst ZrO<sub>2</sub> scale
- Unexpected formation of Ta(C,B) in scale?
- Melt formation: ZrO<sub>2</sub> SiO<sub>2</sub> Ta<sub>2</sub>O<sub>5</sub> all in solution
  - Ta(B,O) phase separated in silica rich areas
  - Si(Ta)O
  - Dendritic structure of Phase V (?) on surface of ZrO<sub>2</sub>, Ta(C,B)
  - Dendritic structure of ZrO<sub>2</sub> in outer scale



## Optimization of TaSi<sub>2</sub> additions

### Oxidation of ZS5TS at 1627°C in air





ZS20TS: 1, 5, and 10 cycles



ZS5TS: 1, 5, and 10 cycles



ZS: 1, 5, and 10 cycles





### Oxidation: 10 minute cycles at 1927°C in stagnant air



ZS5TS: 1, 5, and 7 cycles



ZS20TS: 1 cycle



ZS20TS: 5 cycles



ZS: 1, 5, and 10 cycles



### Summary of oxidation results for ZS5TS

- 5 volume % addition of TaSi<sub>2</sub> to ZS is not enough to promote improved oxidation behavior at 1627°C
  - Oxidation weight gain and appearance similar to ZS (no TaSi<sub>2</sub> additions)
- 5 volume % addition of TaSi<sub>2</sub> to ZS still results in extensive melt formation and undesirable scale morphology during oxidation at 1927°C
- Oxidation behavior of ZS can not be improved at both 1627°C and 1927°C with TaSi<sub>2</sub> additions



## Conclusions: ZrB<sub>2</sub>-SiC-TaSi<sub>2</sub>

- 20 v%TaSi<sub>2</sub> additions to ZrB<sub>2</sub> SiC result in formation of phase separated glass and improved oxidation resistance at 1627°C
- At 1927°C excessive melt formation prevents dimensional stability of oxides formed from ZrB<sub>2</sub> -SiC -TaSi<sub>2</sub>
- TaSi<sub>2</sub> reacts to form (Zr,Ta)B<sub>x</sub>, Ta(C,B) as well as melt solution phases containing Ta, Zr, Si, O, B
- TaSi<sub>2</sub> additions can not be optimized to form both phase separated glass at 1627°C and oxides with dimensional stability at 1927°C.
- More phase stability work needed in UHTC systems



### Acknowledgments

This work was made possible by:

- NASA Next Generation Launch Technology Program, Airframe Technology Project (2004)
- NASA Fundamental Aeronautics Program, Hypersonics Project (2008)